

## Claims

1. Epitaxy equipment comprising an epitaxy chamber under vacuum containing a substrate support and at least one cell under vacuum for evaporation of the epitaxy material closed by a diaphragm presenting at least one opening and communicating with the epitaxy chamber by a connecting flange, comprising moreover a plate positioned opposite said perforated diaphragm, characterized in that said plate is mobile such that the distance of the plate from the exterior surface of the diaphragm is variable and presents a section corresponding to the section of said diaphragm; the molecular beam being formed at the level of a zone surrounding the plate.
2. Epitaxy equipment according to claim 1, characterized in that said plate has the shape of a disc.
3. Epitaxy equipment according to claim 1, characterized in that said plate is mobile in a direction perpendicular to said diaphragm.
4. Epitaxy equipment according to claim 2, characterized in that the course of said plate is 10 millimeters.
5. Epitaxy equipment according to claim 1, characterized in that said plate is mobile angularly so as to form a dihedron variable with the plane of said diaphragm.
6. Epitaxy equipment according to any one of the preceding claims, characterized in that the plate is made of metal or a dielectric material (for example, quartz or boron nitride).

7. Epitaxy equipment according to any one of the preceding claims, characterized in that the plate is actuated by a connecting organ traversing the wall of the epitaxy chamber via an airtight passage.

8. Epitaxy equipment according to any one of the preceding claims, characterized in that the diaphragm presents perforations.

9. Epitaxy equipment according to any one of claims 1 to 6, characterized in that the diaphragm presents an annular opening.